Notice of Allowability	Application No.	Applicant(s)
	10/669,058	SHIMIZU, RYU
	Examiner	Art Unit
	PHUC T DANG	2818
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. THIS
1. \boxtimes This communication is responsive to <u>September 24, 2003</u> .	·	
2. The allowed claim(s) is/are <u>1-9</u> .		
3. \boxtimes The drawings filed on <u>24 September 2003</u> are accepted by	the Examiner.	
 4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient. 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date (be attached Examiner's should be labeled as such in the header according to 37 CFR 1.121(d). 7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL. 		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 032404 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. Interview Summary Paper No./Mail Da' 7. Examiner's Amendr 8. Examiner's Stateme 9. Other	te ment/Comment ent of Reasons for Allowance
PHUCT. DANG Sangfhur PRIMARY EXAMINER		
PRIMARY EXAMINER		

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DETAILED ACTION

Examiner's Statement of Reasons for Allowance

1. Claims 1-9 are allowed.

2. The following is an examiner's statement of reasons for allowance:

With respect to claim 1, the prior art of record, taken alone or in combination, fails to teach or reasonably suggests a method of manufacturing a semiconductor device, comprising a step of substantially filling the via hole and the interconnect trench with a metal layer; wherein the anti-reflection coating is formed to have its thickness at a central portion of the via hole thinner than a distance between the upper surface of the lower interconnect and a bottom portion of the interconnect trench in the forming the anti-reflection coating, in combination with the rest of the limitations of claim 1.

With respect to claim 5, the prior art of record, taken alone or in combination, fails to teach or reasonably suggests a method of manufacturing a semiconductor device, comprising a step of substantially filling the via hole and the interconnect trench with a metal layer; wherein the interconnect trench is formed with the anti-reflection coating formed in the via hole being covered with the resist layer in the forming the interconnect trench, in combination with the rest of the limitations of claim 5.

With respect to claim 9, the prior art of record, taken alone or in combination, fails to teach or reasonably suggests a method of manufacturing a semiconductor device, comprising a step of substantially filling the via hole and the interconnect trench with a metal layer; wherein the anti-reflection coating is formed to have its thickness at a central portion of the via hole greater than a

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limitations of claim 9.

distance between the upper surface of the lower interconnect and a bottom portion of the interconnect trench in the forming the anti-reflection coating, in combination with the rest of the

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

fee. Such submission should be clearly labeled "Comments on Statement of Reasons for

Allowance".

4. Any inquiry concerning this communication or earlier communications from the examiner

should be directed to Phuc T. Dang whose telephone number is (571) 272-1776. The examiner

can normally be reached on 8:00 am-5:00 pm.

5. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

David C. Nelms can be reached on (571) 272-1787. The fax phone numbers for the organization

where this application or proceeding is assigned are 703-872-9306 for regular communications

and After Final communications.

6. Any inquiry of a general nature or relating to the status of this application or proceeding

should be directed to the receptionist whose telephone number is 703-308-0956.

Phuc T. Dang

PD Langshur

Primary Examiner

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